



UNITED STATES PATENT AND TRADEMARK OFFICE

UNITED STATES DEPARTMENT OF COMMERCE
United States Patent and Trademark Office
Address: COMMISSIONER FOR PATENTS
P.O. Box 1450
Alexandria, Virginia 22313-1450
www.uspto.gov

APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/075,218	02/14/2002	Thomas S. Kobayashi	SC11931TP	8301

23125 7590 05/23/2008
FREESCALE SEMICONDUCTOR, INC.
LAW DEPARTMENT
7700 WEST PARMER LANE MD:TX32/PL02
AUSTIN, TX 78729

EXAMINER

FULK, STEVEN J

ART UNIT	PAPER NUMBER
----------	--------------

2891

MAIL DATE	DELIVERY MODE
-----------	---------------

05/23/2008

PAPER

Please find below and/or attached an Office communication concerning this application or proceeding.

The time period for reply, if any, is set in the attached communication.

**UNITED STATES DEPARTMENT OF COMMERCE****U.S. Patent and Trademark Office**

Address : COMMISSIONER FOR PATENTS
P.O. Box 1450
Alexandria, Virginia 22313-1450

APPLICATION NO./ CONTROL NO.	FILING DATE	FIRST NAMED INVENTOR / PATENT IN REEXAMINATION	ATTORNEY DOCKET NO.
10075218	2/14/2002	KOBAYASHI ET AL.	SC11931TP

FREESCALE SEMICONDUCTOR, INC.
LAW DEPARTMENT
7700 WEST PARMER LANE MD:TX32/PL02
AUSTIN, TX 78729

EXAMINER

Steven J.. Fulk

ART UNIT	PAPER
----------	-------

2891	20080521
------	----------

DATE MAILED:

Please find below and/or attached an Office communication concerning this application or proceeding.

Commissioner for Patents

The Applicant is invited to review the Non-Patent Literature made of record as of this communication. Wolf teaches that silicon oxide was a well known material used as passivation layers in semiconductor devices (pp. 273-275). While the reference notes that phosphorus can be added to reduce stress in the silicon oxide passivation layer, it was nonetheless known to use silicon oxide as the passivation material.

Attachments:
PTO-892
Non-patent literature document

/BRADLEY W BAUMEISTER/
Supervisory Patent Examiner, Art Unit 2891